

L Number	Hits	Search Text	DB	Time stamp
1	213	((((hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum)) and ((Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4) with nitr\$4)))) and (mask or photomask or reticle) and (resist or photoresist)) and ((430/5).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/06 16:20
2	182	(430/296.ccls. and ((Resist or photoresist) with ((hard or metal or etch\$3) adj (layer or film or mask)))) and (Cr or chrom\$4 or W or tungsten or Ta or tantalum)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/06 16:25
3	122	(((430/311).CCLS.) and ((hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum)) and (Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4) with nitr\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/06 16:26
4	86	(((430/322).CCLS.) and ((hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum)) and (Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4) with nitr\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/06 16:28
5	122	(216/53).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/05/06 16:28
6	33	((216/53).CCLS.) and (mask or photomask or reticle)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2004/05/06 16:29
-	1	09/683929	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/22 16:52
-	204	(UTR or (thin near (resist or photoresist))) and (((hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum)) and ((Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4) with nitr\$4))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/28 14:27
-	1746	(((hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum)) and ((Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4) with nitr\$4)))) and (mask or photomask or reticle).ti,ab.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/28 14:27
-	75	(UTR or (thin near (resist or photoresist))) and (((hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or tantalum)) and ((Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4) with nitr\$4)))) and (mask or photomask or reticle).ti,ab.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/04/28 14:28